

## **Amendments to the Claims**

### **In the Claims:**

Please amend the claims as follows (the changes in these Claims are shown with strikethrough for deleted matter and underlines for added matter).

1. (Four Times Amended) A plasma treatment equipment having a chamber for performing plasma treatment, the plasma treatment equipment comprising:  
a plasma excitation electrode to which a power for plasma excitation is supplied,  
the plasma excitation electrode being provided in the chamber; and  
a susceptor electrode that is opposed to the plasma excitation electrode provided in the chamber, the susceptor electrode having the same DC potential as that of a chamber wall of the chamber, the susceptor electrode being an electrode into which a high frequency electric current based on the power for plasma excitation flows after passing through a plasma space;  
wherein the chamber wall of the chamber and the susceptor electrode are AC shorted to each other by a plurality of metal plates, the susceptor electrode is connected to the chamber wall of the chamber by a bellows disposed outside the chamber, the plurality of metal plates are configured so that the plasma treatment equipment have a susceptor impedance less than 15Ω using a power source having frequency higher than 13.56MHz[Plasma treatment equipment in which a chamber wall and a susceptor electrode having the same DC potential are AC shorted to each other].

4. (Amended) The plasma treatment equipment according to claim 3, wherein [said susceptor electrode is shorted to said chamber wall by a metal plate, said] each metal plate [being] is connected between the short point on the bottom wall and a second short point on a shield of the susceptor electrode.

5. (Amended) The plasma treatment equipment according to claim [3]4, wherein the said metal plate is inclined with respect to the bottom wall, and an angle formed between said metal plate and the bottom wall is less than 45 degrees.

13. (New) A plasma treatment equipment having a chamber for performing plasma treatment, the plasma treatment equipment comprising:  
a plasma excitation electrode to which a power for plasma excitation is supplied,  
the plasma excitation electrode being provided in the chamber;  
a susceptor electrode that is opposed to the plasma excitation electrode provided in the chamber; and  
an electrode shield of the susceptor electrode in the chamber,  
wherein at least one of the susceptor electrode and the electrode shield thereof has the same DC potential as that of a chamber wall of the chamber,  
the susceptor electrode being an electrode into which a high frequency electric current based on the power for plasma excitation flows after passing through a plasma space,  
the chamber wall of the chamber and at least one of the susceptor electrode and the electrode shield thereof are AC shorted to each other by a plurality of metal plates,  
and  
the susceptor electrode is connected to the chamber wall of the chamber by a bellows disposed outside the chamber, the plurality of metal plates are configured so that the plasma treatment equipment have a susceptor impedance less than  $15\Omega$  using a power source having frequency higher than 13.56MHz.

23. (New) A plasma treatment equipment having a chamber for performing plasma treatment, the plasma treatment equipment comprising:  
a plasma excitation electrode to which a power for plasma excitation is supplied,  
the plasma excitation electrode being provided in the chamber;  
a susceptor electrode that is opposed to the plasma excitation electrode provided in the chamber; and  
an electrode shield of the susceptor electrode in the chamber, the electrode shield disposed adjacent to the susceptor electrode,  
wherein at least one of the susceptor electrode and the electrode shield thereof has the same DC potential as that of a chamber wall of the chamber,

the susceptor electrode being an electrode into which a high frequency electric current based on the power for plasma excitation flows after passing through a plasma space,

the chamber wall of the chamber and at least one of the susceptor electrode and the electrode shield thereof are AC shorted to each other by a plurality of metal plates, each metal plate having a first end connected to a first short point on the shield and a second end connected to a second short point on an inner surface of the bottom wall of the chamber, and

the susceptor electrode is connected to the chamber wall of the chamber by a bellows disposed outside the chamber, the plurality of metal plates are configured so that the plasma treatment equipment have a susceptor impedance less than  $15\Omega$  using a power source having frequency higher than 13.56MHz.

24. (Withdrawn) The plasma treatment equipment according to claim 1, wherein the plurality of metal plates are mesh forms disposed in point symmetry with respect to the center of the shield.